

ABSTRACT OF THE DISCLOSURE

A method for manufacturing an object mask which is used in an electron beam proximity exposure apparatus comprising an electron beam source which emits a collimated electron beam, the object mask having an aperture which is arranged on a path of the electron beam, and a stage which holds and moves an object, wherein the object mask is arranged in proximity to a surface of the object and a pattern corresponding to the aperture of the object mask is exposed on the surface of the object with the electron beam having passed through the aperture, the method comprising the steps of: manufacturing a master mask having an aperture of a pattern identical with the object mask; and manufacturing a child mask by exposing an aperture pattern identical with the master mask by using the master mask in an electron beam proximity exposure method, wherein the child mask is used as the object mask. Thus, a manufacturing method of the masks for the electron beam proximity exposure at reduced costs is accomplished.